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[Continued on next page]

(54) Title: RELAXATION AND TRANSFER OF STRAINED LAYERS

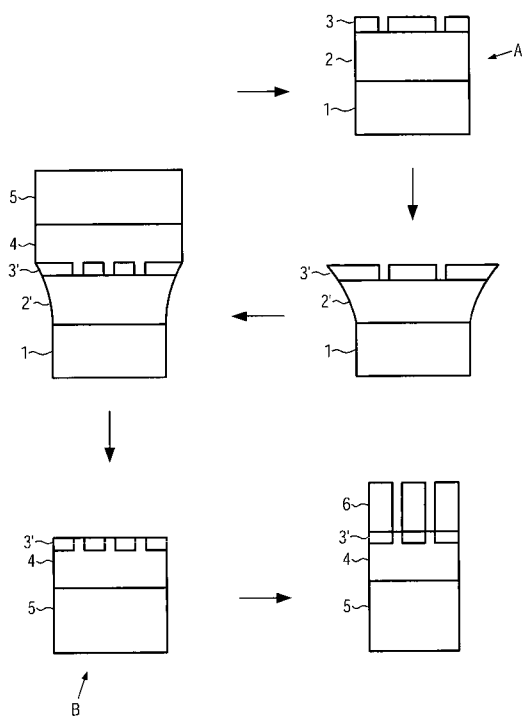


FIG. 1

(57) Abstract: The present invention relates a method for the formation of at least partially relaxed strained material on a target substrate, comprising the subsequently performed steps of forming islands from a strained material layer on an intermediate substrate, at least partially relaxing the strained material islands by a first heat treatment and transferring the at least partially relaxed strained material islands to the target substrate.

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**A. CLASSIFICATION OF SUBJECT MATTER**

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According to International Patent Classification (IPC) or to both national classification and IPC

**B. FIELDS SEARCHED**

Minimum documentation searched (classification system followed by classification symbols)  
H01L

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal

**C. DOCUMENTS CONSIDERED TO BE RELEVANT**

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X	US 2007/069225 A1 (KRAMES MICHAEL R [US] ET AL) 29 March 2007 (2007-03-29)	15-16
Y	paragraph [0002] - paragraph [0005] paragraph [0019] - paragraph [0023]; figure 1; tables 1,2 page 4, left-hand column, line 17 - line 23 paragraph [0034] - paragraph [0035]; figure 9 paragraph [0036] - paragraph [0037]; figures 4,5 paragraph [0039] - paragraph [0044]; figures 7,8 paragraph [0047] - paragraph [0048] ----- -/--	1-11, 13-14

Further documents are listed in the continuation of Box C.

See patent family annex.

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C(Continuation). DOCUMENTS CONSIDERED TO BE RELEVANT		
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# INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No <b>PCT/EP2009/004792</b>
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